

Abstract Submitted  
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**Deposition of Metals via Chemical Vapor Deposition** DAVID MCKENNA, DAVID ALLRED, ROBERT DAVIS, Brigham Young University — In an effort to develop a CVD process to deposit metals on various substrates I have created a multi-gas system with a computer controlled interface. This allows the use of up to 5 different gasses as reactants or carriers for the CVD process. I have also fabricated a specialized heated [gas flow chamber wherein solid materials can be volatilized with heat and carried to the substrate by gas also heated in the chamber. I will present the design of this chamber and it's function in our current deposition process along with preliminary results of the deposition of tungsten on various substrates.

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